

<b>INFORMATION DISCLOSURE CITATION</b> 		Atty. Docket No. NMTC-0756	Serial No. 10/016,837
		Applicant ZHANG, Youping	
		Filing Date 12/12/2001	Group 2825
<b>OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)</b>			
EXAMINER'S INITIALS	CITATION		
BB	Ackmann, P., et al., "Phase Shifting and Optical Proximity Corrections to Improve CD Control on Logic Devices in Manufacturing for Sub 0.35 um I-Line", SPIE, Vol. 3051, pp. 146-153, March 12-14, 1997.		
BB	Lithas, "Lithas: Optical Proximity Correction Software" (2 pages).		
BB	Precim, "Proxima System", Precim Company, Portland, Oregon (2 pages).		
BB	Precim, "Proxima Wafer Proximity Correction System", Precim Company, Portland, Oregon (2 pages).		
BB	Rieger, M., et al., "Mask Fabrication Rules for Proximity-Corrected Patterns", Precim Company, Portland, Oregon (10 pages).		
BB	Rieger, M., et al., "Using Behavior Modeling for Proximity Correction", Precim Company, Portland, Oregon (6 pages).		
BB	Cobb, et al., "Fast Sparse Aerial Image Calculation for OPC", SPIE, Vol. 2621, pp. 534-544, September 20-22, 1995.		
BB	Lucas, K., et al., "Model Based OPC for 1st Generation 193nm Lithography", Motorola Inc., IDT assignee to IMEC (12 pages).		
BB	Sturman, J., et al., "Quantifying Proximity and Related Effects in Advanced Wafer Processes", Precim Company, Hewlett Packard Labs (9 pages).		
BB	Sugawara, M., et al., "Practical Evaluation of Optical Proximity Effect Correction by EDM Methodology", Sony Corporation (11 pages).		
BB	Saleh, B., et al., "Reduction of Errors of Microphotographic Reproductions by Optimal Corrections of Original Masks", Optical Engineering, Vol. 20, No. 5, pp. 781-784, September/October 1981.		
BB	Fu, C.C., et al., "Enhancement of Lithographic Patterns by Using Serif Features", IEEE, Transactions On Electron Devices, Vol. 38, No. 12, pp. 2599-2603, December 1991.		
BB	Harafuji, K., et al., "A Novel Hierarchical Approach for Proximity Effect Correction in Electron Beam Lithography", IEEE, Vol. 12, No. 10, pp. 1508-1514, October 1993.		
BB	Rieger, M., et al., "System for Lithography Proximity Compensation", Precim Company, Portland, Oregon, September 1993 (28 pages).		

EXAMINER:

Burhan Bawani

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<b>INFORMATION DISCLOSURE CITATION</b> <b>PTO-1449</b>		Atty. Docket No. NMTC-0756	Serial No. 10/016,837
		Applicant ZHANG, Youping	Group 2825
		Filing Date 12/12/2001	
			
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<b>OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)</b>			
EXAMINER'S INITIALS	CITATION		
BB	Stirniman, J., et al., "Fast Proximity Correction with Zone Sampling", SPIE, Vol. 2197, pp. 294-301 (1994).		
BB	Stirniman, J., et al., "Optimizing Proximity Correction for Wafer Fabrication Processes", SPIE, Photomask Technology And Management, Vol. 2322, pp. 239-246 (1994).		
BB	Stirniman, J., et al., "Wafer Proximity Correction and Its Impact on Mask-Making", Bacus News, Vol. 10, Issue 1, pp. 1, 3-7, 10-12, January 1994.		
BB	Henderson, R., et al., "Optical Proximity Effect Correction: An Emerging Technology", Microlithography World, pp. 6-12 (1994).		
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BB	Morimoto, H., et al., "Next Generation Mask Strategy - Technologies are Ready for Mass Production of 256MDRAM?", SPIE, Vol. 3236, pp. 188-189 (1997).		
BB	Park, C., et al., "An Automatic Gate CD Control for a Full Chip Scale SRAM Device", SPIE, Vol. 3236, pp. 350-357 (1997).		
BB	Dolainsky, C., et al., "Application of a Simple Resist Model to Fast Optical Proximity Correction", SPIE, Vol. 3051, pp. 774-780 (1997).		
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BB	Asai, N., et al., "Proposal for the Coma Aberration Dependent Overlay Error Compensation Technology", Jpn. J. Appl. Phys., Vol. 37, pp. 6718-6722 (1998).		

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		Filing Date 12/12/2001	Group 2825

#### FOREIGN PATENT DOCUMENTS

EXAMINER'S INITIALS	PATENT NO.	DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION	
						YES	NO
bb	JP 3-80525	4/5/1991	JP			<input type="checkbox"/>	<input type="checkbox"/>
bg	WO 00/67074 A1	11/9/2000	WO			<input type="checkbox"/>	<input type="checkbox"/>
GB	GB 2,324,169 A	10/14/1998	GB			<input type="checkbox"/>	<input type="checkbox"/>

EXAMINER: Brendan Bowen

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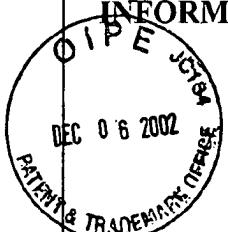
<b>INFORMATION DISCLOSURE CITATION</b> PTO-1449 JUL 15 2002 JC68 PATENT & TRADEMARK OFFICE		Atty. Docket No. NMTC-0756	Serial No. 10/016,837	RECEIVED JUL 16 2002 TECHNOLOGY CENTER 2800		
		Applicant ZHANG, Youping				
		Filing Date 12/12/2001	Group 2825			
<b>U.S. PATENT DOCUMENTS</b>						
EXAMINER'S INITIALS	PATENT NO.	DATE	NAME	CLASS	SUBCLASS	FILING DATE
SG	5,631,110	5/20/1997	Shioiri, et al.	430	5	6/5/1995
BB	5,682,323	10/28/1997	Pasch, et al.	364	491	3/6/1995
BB	5,723,233	3/3/1998	Garza, et al.	430	5	2/27/1996
BB	5,815,685	9/29/1998	Kamon	395	500	9/15/1995
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BB	5,991,006	11/23/2000	Tsudaka	355	53	10/27/1997
BB	6,081,658	6/27/2000	Rieger, et al.	395	500.22	12/31/1997
BB	6,289,499	9/11/2001	Rieger, et al.	716	21	1/7/2000
BB	6,243,855 B1	6/5/2001	Kobayashi, et al.	716	19	9/29/1998
BB	6,249,597 B1	6/19/2001	Tsudaka	382	144	12/17/1998

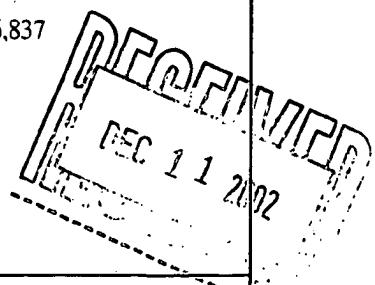
EXAMINER: Brenda Brown

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EXAMINER'S INITIALS	PATENT NO.	DATE	NAME	CLASS	SUBCLASS	FILING DATE
BG	6,014,456	1/11/2000	Tsudaka	382	144	7/15/1996
BG	6,154,563	11/28/2000	Tsudaka	382	144	12/17/1998
BG	6,298,473 B1	10/2/2001	Ono, et al.	716	21	12/3/1998
BG	6,453,457 B1	9/17/2002	Pierrat, et al.	716	19	9/29/2000
BG	2002/0100004 A1	7/25/2002	Pierrat, et al.	716	5	3/15/2002

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EXAMINER: Brian Burns

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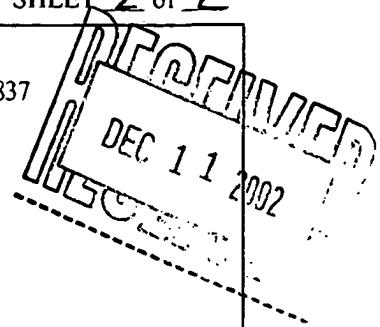
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EXAMINER'S INITIALS	CITATION
Bb	Cobb, N., et al., "Fast, Low-Complexity Mask Design", SPIE, Vol. 2440, pp. 313-327, February 22-24, 1995.
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